

IN THE CLAIMS:

Claim 1 (currently amended): In a power supply circuit for plasma generation by which said plasma is generated due to discharge occurred between discharge generating electrodes composed of first and second electrodes by applying an alternating high voltage to said discharge generating electrodes, said power supply circuit for plasma generation comprising:

said discharge generating electrodes composed of two or more first electrodes and one or more second electrodes; and

an alternating high voltage generating circuit to generate said alternating high voltage applied between said first and second electrodes of said discharge generating electrodes;

wherein one selected from a ~~condenser~~ (a capacitor[[]]) and a ~~coil~~ (an inductor[[]] are)] is connected in series between said first electrode and one output end of said alternating high voltage generating circuit.

Claim 2 (currently amended): The power supply circuit for plasma generation according to claim 1, wherein said alternating high voltage generating circuit includes a high frequency transformer, two or more output circuits brunched in parallel from one end side of a secondary side coil of said high frequency transformer are connected to said first electrodes, each of said output circuits is formed by a series connection of said ~~condenser~~ capacitor and said [[coil]] inductor, and said second electrode is connected to another end side of said secondary side coil.

Claim 3 (currently amended): The power supply circuit for plasma generation according to claim 1, wherein said alternating high voltage generating circuit includes a high frequency transformer, a plurality of secondary side coils are arranged at a secondary side of said high frequency transformer, one or more output circuits brunched in parallel from one end side of each secondary side coil are connected to said first electrodes, each of said output circuits is formed by a series connection of said ~~condenser~~ capacitor and said [[coil]] inductor, and said second electrode is connected to another end side of said secondary side coil.

Claim 4 (currently amended): In a plasma generating apparatus by which said plasma is generated due to discharge occurred between discharge generating electrodes composed of first and second electrodes by applying an alternating high voltage to said discharge generating electrodes, said plasma generating apparatus comprising:

said discharge generating electrodes composed of two or more first electrodes and one or more second electrodes; and

an alternating high voltage generating circuit to generate said alternating high voltage applied between said first and second electrodes of said discharge generating electrodes;

wherein ~~a condenser~~ (a capacitor[[ ]]) and ~~a coil~~ (an inductor[[ ]]) are connected in series between said first electrode and one output end of said alternating high voltage generating circuit.

Claim 5 (currently amended): The plasma generating apparatus according to claim 4, wherein said alternating high voltage generating circuit includes a high frequency transformer, two or more output circuits brunched in parallel from one end side of a secondary side coil of said high frequency transformer are connected to said first electrodes, each of said output circuits is formed by a series connection of said ~~condenser~~ capacitor and said [[coil]] inductor, and said second electrode is connected to another end side of said secondary side coil.

Claim 6 (currently amended): The plasma generating apparatus according to claim 4, wherein said alternating high voltage generating circuit includes a high frequency transformer, a plurality of secondary side coils are arranged at a secondary side of said high frequency transformer, one or more output circuits brunched in parallel from one end side of each secondary side coil are connected to said first electrodes, each of said output circuits is formed by a series connection of said ~~condenser~~ capacitor and said [[coil]] inductor, and said second electrode is connected to another end side of said secondary side coil.

Claim 7 (original): The plasma generating apparatus according to claim 4, 5 or 6, wherein either one electrode of said first electrode or said second electrode has a geometry surrounding the other electrode, and a tip end portion of said one electrode is formed into a nozzle shape for emitting said plasma generated between said electrodes.

Claim 8 (original): The plasma generating apparatus according to claim 4, 5 or 6, wherein said first electrode and said second electrode are facing, so that said plasma generated between said electrodes is emitted from an open end side of said electrodes.

Claim 9 (previously presented): The plasma generating apparatus according to claim 4, 5 or 6, wherein said plasma generating apparatus further includes a fluid supplying means to supply a fluid into a generation area of said plasma generated between said electrodes.

Claim 10 (previously presented): The plasma generating apparatus according to claim 4, 5 or 6, wherein each of said electrode pairs is arranged in a predetermined direction.

Claim 11 (currently amended): A plasma processing apparatus characterized in that said plasma processing apparatus characterized in that said plasma processing apparatus includes the plasma generating apparatus according to any of claims 4[[ to 10]], 5 or 6, and an object to be processed is irradiated with said plasma generated between said electrodes.

Claim 12 (previously presented): The plasma processing apparatus according to claim 11, wherein each of said electrodes is arranged so that emitting directions of said plasma generated between said electrodes are facing each other.

Claim 13 (previously presented): The plasma processing apparatus according to claim 11, wherein each of said electrodes is arranged so that emitting positions of said plasma generated between said electrodes are formed in a spiral.

Claim 14 (previously presented): The plasma processing apparatus according to claim 11, wherein an aggregate of said electrodes is formed in a bundle by assembling emitting portions of said plasma generated between said electrodes.

Claim 15 (previously presented): The plasma processing apparatus according to claim 11, wherein said plasma processing apparatus further includes an adjusting means for adjusting an irradiating distance to said object to be processed irradiated with said plasma emitted from between said electrodes.

Claim 16 (previously presented): The plasma processing apparatus according to claim 11, wherein said plasma processing apparatus further includes an adjusting means for adjusting a direction irradiating said object to be processed with said plasma emitted from each space between said electrodes.

Claim 17 (currently amended): The plasma processing apparatus according to ~~any of claims~~ claim 11[[ to 14]], wherein said plasma processing apparatus further includes a passageway of object to be processed distributing said object to be processed in vicinity of each of said electrodes.

Claim 18 (original): The plasma processing apparatus according to claim 14, wherein said plasma processing apparatus further includes a passageway of object to be processed distributing said object to be processed to the center of said aggregate of said electrodes.

Claim 19 (currently amended): A plasma processed object characterized in that said plasma processed object is produced by use of the plasma processing apparatus according to ~~any of claims~~ claim 11[[ to 18]], and said plasma processed object is produced by plasma processing of said object to be processed.